

ABSTRACT

An anti-backflow apparatus, comprising a cup (141), a protective cover (142) and a gas exhaust unit. The upper portion of the cup (141) is provided with an opening (1411). The protective cover (142) covers the opening (1411) of the cup (141) and is provided with a liquid receiving port (1421) and a gas exhaust port (1422). The liquid receiving port (1421) is used for a nozzle (130) to drip chemical liquid into the cup (141). The gas exhaust unit is connected to the inside of the cup (141) through the gas exhaust port (1422) of the protective cover (142), so as to suck volatile gas inside the cup (141), which can effectively prevent the volatile gas inside the cup (141) from flowing back into a process chamber (10) of a substrate processing device (1), and can prevent the volatile gas from corroding the surface of a substrate (W) in the process chamber (10). Also disclosed is a substrate processing device (1) having the anti-backflow apparatus.